



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Rosalie A. Centeno
Rosalie A. Centeno Secretary

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In the Application of John Oshinowo et al

Ser.No.: 09/913,985

For: APPARATUS AND METHOD FOR TREATING SUBSTRATES

Filed on: AUGUST 17, 2001

Assistant Commissioner for Patents

Washington, DC 20231

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PRELIMINARY AMENDMENT

Sir:

Prior to examination, please amend the above-identified application as follows.

IN THE SPECIFICATION:

On page 2, lines 5 - 16, please replace the existing paragraph with the following paragraph:

B1

--JP-A-61-133633 discloses an apparatus for the treatment of semiconductor wafers using three identical treatment tanks that are supplied with treatment fluid via a common supply unit. The treatment tanks are sequentially used for the treatment of the wafers in such a way that at any point in time only a single tank is used for the treatment of wafers. The remaining tanks are held in readiness in order after conclusion of a specific number of treatment cycles in the already used tank to be used as the treatment tank. This apparatus requires space for three treatment tanks, although at any given point in time only one of the tanks is used for the treatment of wafers. This high requirement for space leads to high costs for the apparatus, which are generally operated in expensive clean or super-clean rooms.--